Axcelis Debuts Ion Source Technology

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Axcelis Technologies AG has introduced its Eterna ELS (extended life source) ion source technology, which the company said is capable of cutting operational costs by 50 percent as well as doubling the lifetime of consumable parts.

According to Beverly, Mass.-based Axcelis, the Eterna ELS is able to deliver much higher reliability rates than other ion implanter sources. Conexant Systems Inc. said it has seen improvements in the company's manufacturing operations since it began using the system.

"Since using the new Eterna ELS, we have experienced exceptional source performance across the complete spectrum of our manufacturing applications," said Haissam Bazzaz, manager of equipment and process hivac/diffusion, Conexant Semiconductor, in a statement. "The system has doubled the average source life across the board on GSD high current, 8200P medium current and GSD/HE high energy systems, comparing to our previous sources, and on few occasions we have seen sources reaching triple life, depending on the product mix."

Redesigned filaments and insulators extend the Eterna ELS lifetime by as much as 100 percent in most applications, the company said. The technology offers streamlined alignment procedures and new ergonomic handles to improve repeatability and simplify tool operation. It also offers a selection of chamber, cathode and liner options. The Eterna ELS components can be phased in as current inventory is consumed, allowing for an uninterrupted supply of new parts at no additional cost.